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IN AN APPLICATION

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Docket Number (Optional)

HNP 201

Application Number

10/553, 728

Applicant

KAROLA RICHTER ET AL

Fullar Date

1/31/2006

### Group Art Unit

1765

## U.S. PATENT DOCUMENTS

[illegible]

## FOREIGN PATENT DOCUMENTS

[illegible]

## OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

[illegible]

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Form PTO-1449

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Docket Number (Optional)  
HMP201

Applicant RICHTER et al

Filing Date 10/14/05

## Group Art Unit

## U.S. PATENT DOCUMENTS

[illegible]

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
IPG/	0 8 1 8 6 0 9 5	07/16/96	JAPAN	HOIL	21/3065		
IPG/	0 4 0 2 8 2 2 9	01/30/92	JAPAN	HOIL	21/3205		

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

IPG/	AACHBOUN et al, "Deep anisotropic etching of silicon", J. Vac. Sci. Technol. A 17 (4), Jul/Aug 1999, pp. 2270-2273
IPG/	AYON et al.; "Application of the floating effect in the micromachining..", J. Vac. Sci. Technol. A 17(4), Jul/Aug 1999; pp. 2274-2279
IPG/	ZIJLSTRA et al. "Fabrication of two-dimensional photonic crystal waveguides..", J. Vac. Sci. Technol. B 17(6) Nov/Dec 1999 pp. 2734-2739
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08/23/2007

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### Group Art Unit

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IPGI	VOLLAND et al. "DRY ETCHING WITH GAS HOPPING ..."
	J. Vac. Sci. Technol. B 17 (6) Nov/Dec 1999 pp 2768-2771
IPGI	BOEING, "Fundamentals of Plasma Chemistry and Technology"
	The Research Institute of Plasma Chemistry, Carlsbad, CA, p. 174
IPGI	CHANG et al, "Highly selective etching for polysilicon ..."
	J. Appl. Phys 80 (5), 1 September 1996 pp 3048 - 3055

08/23/2007

Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE





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## U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

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IPG/	H.v. Boeing, FUNDAMENTALS OF PLASMA CHEMISTRY AND TECHNOLOGY
	p. 174, The Research Institute of Plasma Chemistry, Carlsbad, CA
IPG/	J. W. RANGELOW et al; J. VAC. SCI. TECHNOL, B13(6)
	Nov/Dec 1995, pp 2394-2399
IPG/	K. M. CHANG et al; JOURNAL OF APPLIED PHYSICS
	SEPT 1, 1996, Vol. 80, Issue 5, pp 3048-3055

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